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(54) Title: SYSTEMS, SETUPS, UNITS AND METHODS FOR BEAM PROFILE MODIFICATION

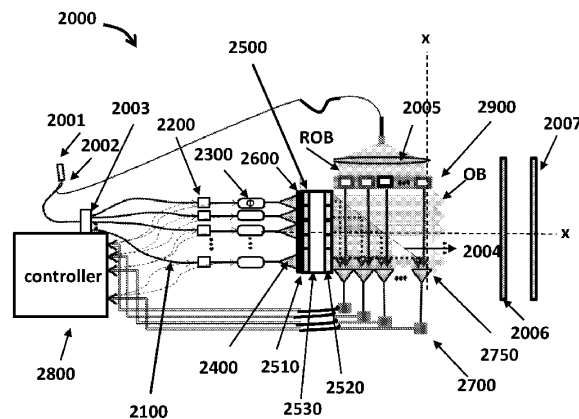


Fig. 13

(57) Abstract: A modification setup including an array (2500) of modification units (320), each positioned and configured to: cause light of an input optical beam (IB) to pass through a corresponding input surface (IS1) of the respective modification unit, in a manner that reduces exceeding of its light, from a first effective aperture of the input surface; and modify beam profile of the input optical beam, to form an intermediate optical beam (IMB) having a beam profile of illumination distribution factor that is higher than that of the input optical beam. An output surface (IS2) of the modification unit, located at a distance D from the input surface is configured and positioned such that the intermediate optical beam passes through the output surface at increased illumination cover area and decreased exceeding from a second effective aperture of the output surface. Each input beam may be collimated (311, 2400) before entering the input surface of a corresponding modification unit.

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